

**Supporting information for ‘Converting Molecular Layer Deposited  
alucone films into Al<sub>2</sub>O<sub>3</sub>/alucone inorganic/hybrid multilayers by  
plasma densification.’**

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## SUPPORTING INFORMATION

### LIST OF FIGURES

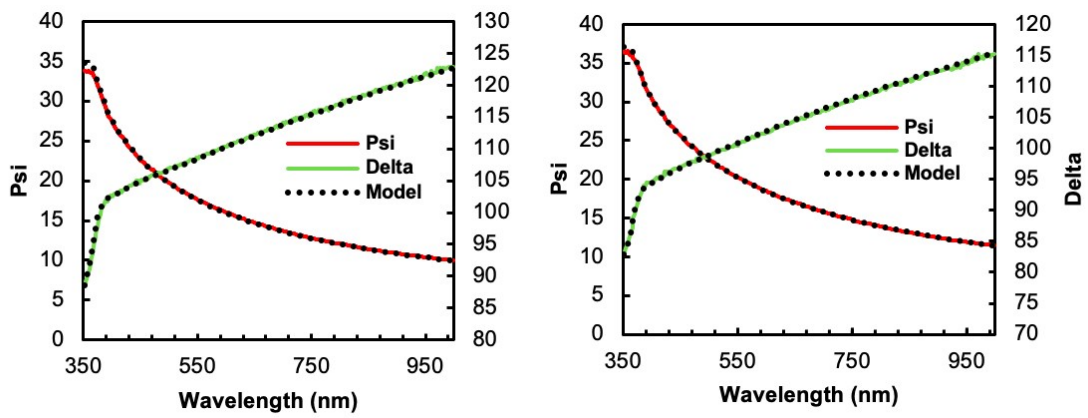


Figure S1. Raw psi/delta ellipsometry data of first (a) and last point (b) of an example (Figure 1) O<sub>2</sub> plasma densification process.

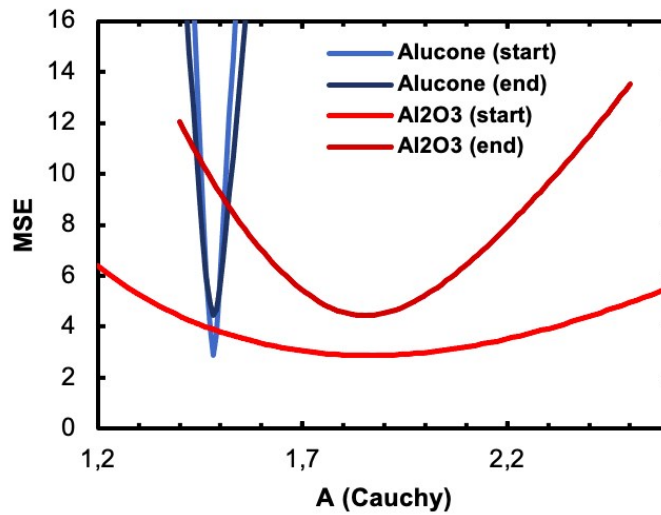
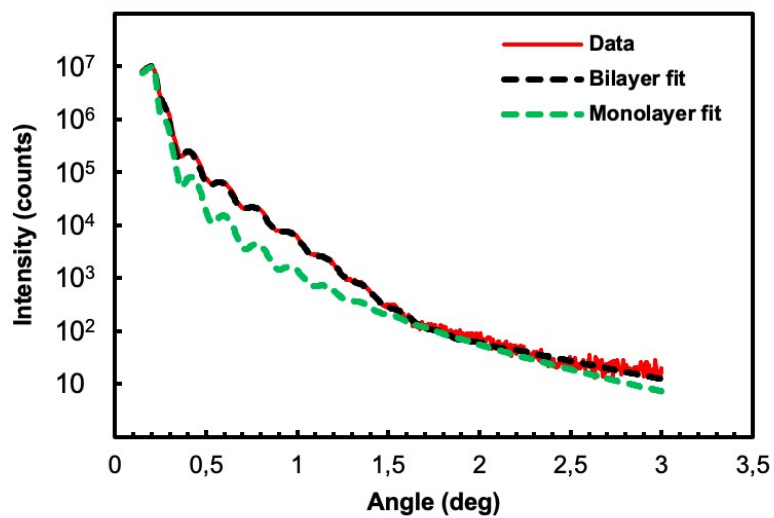
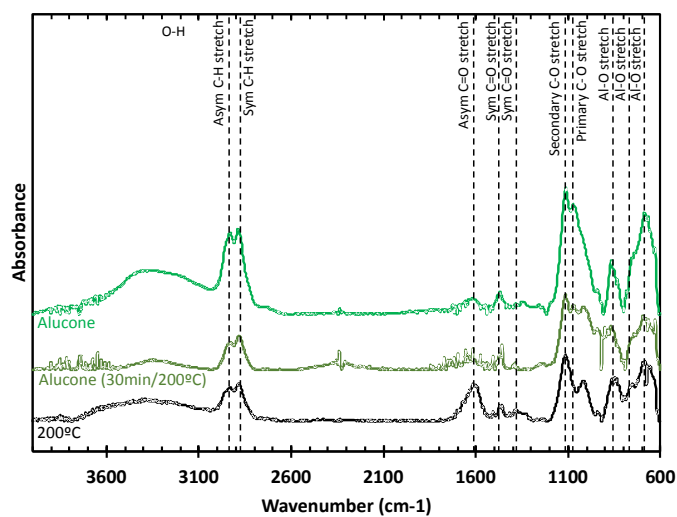


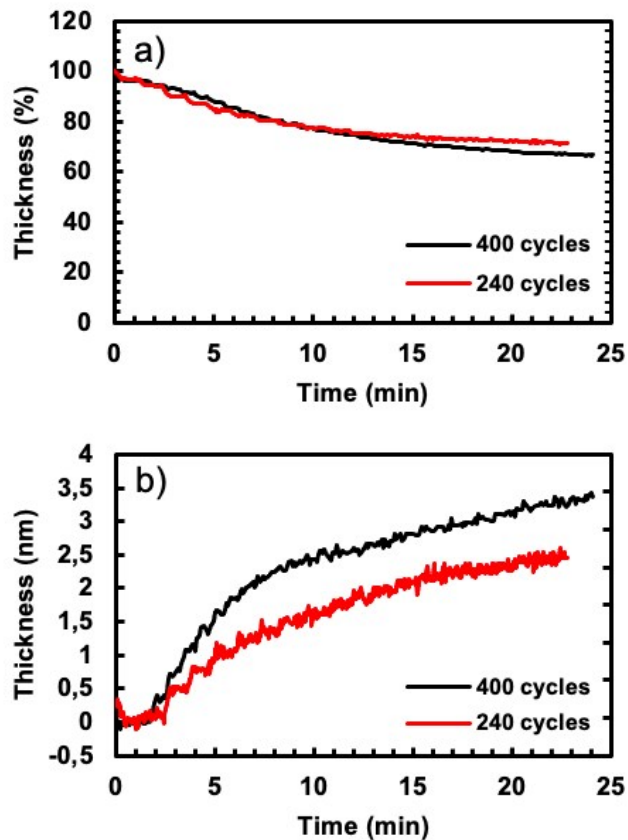
Figure S2. Ellipsometry error variation with respect to changing alucone/Al<sub>2</sub>O<sub>3</sub> refractive indexes.



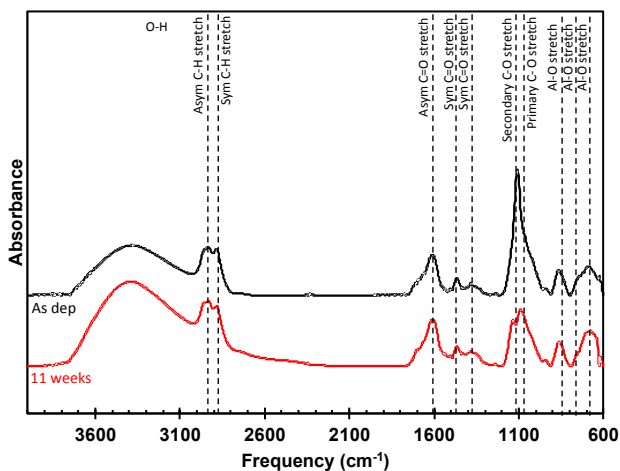
**Figure S3.** X-ray reflectivity data of a sample after densification, fitted with a monolayer model (green) and a bilayer model (black).



**Figure S4.** FTIR comparison between a pristine alucone, an alucone deposited and left for 30 minutes inside the reactor chamber at 200°C; and an alucone densified at 200°C.



**Figure S5.** a) Alucone removal in percentage (%) of original film remaining at different thickness levels. b)  $\text{Al}_2\text{O}_3$  formation in nm with plasma exposure time (normalized).



**Figure S6.** FTIR comparison of an alucone/ $\text{Al}_2\text{O}_3$  multistack as-deposited (black) and after aging in air for 11 weeks (red).



## XRR TABLES

**Table S1.** Thickness values of alucone/ $\text{Al}_2\text{O}_3$  pre- and post-densification, densified at different temperatures. Data was collected by SE (top) and XRR (bottom).

Film	Technique used	50°C	100°C	200°C
Original alucone thickness (nm)	SE	25.27	31.25	30.09
Alucone thickness after densification (nm)	SE	17.41	22.33	14.96
$\text{Al}_2\text{O}_3$ thickness after densification (nm)	SE	2.70	2.63	2.4
Alucone/Original thickness ratio		0.69	0.71	0.50

Original alucone thickness (nm)	SE	25.27	31.25	30.09
Alucone thickness after densification (nm)	XRR	17.77	21.11	21.82
$\text{Al}_2\text{O}_3$ thickness after densification (nm)	XRR	2.37	2.18	2.78
Alucone/Original thickness ratio		0.70	0.68	0.73

**Table S2.** Thickness values of alucone/ $\text{Al}_2\text{O}_3$  pre- and post-densification, densified at different plasma power settings. Data was collected by SE (top) and XRR (bottom).

Film	Technique used	140W	75W
Original alucone thickness (nm)	SE	30.94	31.25
Alucone thickness after densification (nm)	SE	21.57	22.33
$\text{Al}_2\text{O}_3$ thickness after densification (nm)	SE	3.00	2.63
Alucone/Original thickness ratio		0.70	0.71

Original alucone thickness (nm)	SE	30.94	31.25
Alucone thickness after densification (nm)	XRR	20.78	21.11
$\text{Al}_2\text{O}_3$ thickness after densification (nm)	XRR	1.92	2.18
Alucone/Original thickness ratio		0.67	0.68

**Table S3.** Thickness values of alucone/ $\text{Al}_2\text{O}_3$  pre- and post-densification, densified at different thickness levels. Data was collected by SE (top) and XRR (bottom).

Film	Technique used	240cyc	400cyc
Original alucone thickness (nm)	SE	31.25	44.42
Alucone thickness after densification (nm)	SE	22.33	29.61
$\text{Al}_2\text{O}_3$ thickness after densification (nm)	SE	2.63	3.01
Alucone/Original thickness ratio		0.71	0.67

Original alucone thickness (nm)	SE	31.25	44.42
Alucone thickness after densification (nm)	XRR	21.11	28.71
$\text{Al}_2\text{O}_3$ thickness after densification (nm)	XRR	2.18	2.74
Alucone/Original thickness ratio		0.68	0.65